

IN THE CLAIMS

Please amend claims 1, 11, 15 and 16.

Please amend the following claims:

1. (Amended) A slurry, comprising a mixture of:

B1 a surfactant containing an alkyltrimethylammonium cation; a chelating buffer system; an abrasive; an oxidizer; and a corrosion inhibitor; wherein the slurry has a pH between 2.5 and 7.0.

2. The slurry of Claim 1, wherein the surfactant comprises cetyltrimethylammonium bromide dissolved in the mixture.

3. The slurry of Claim 1, wherein the surfactant comprises cetyltrimethylammonium cations and halogen anions.

4. The slurry of Claim 3, wherein the abrasive comprises silica, the corrosion inhibitor comprises benzotriazole, and the oxidizer comprises hydrogen peroxide dissolved in the mixture.

5. The slurry of Claim 1, wherein the chelating buffer system comprises ammonium bicarbonate and potassium citrate dissolved in the mixture.

6. The slurry of Claim 1, wherein the chelating buffer system is selected from the group consisting of citric acid/potassium citrate, and ammonium bicarbonate/potassium citrate.

7. The slurry of Claim 1, wherein the corrosion inhibitor is selected from the group consisting of benzotriazole and cetyltrimethylammonium bromide.

8. The slurry of Claim 1, wherein the surfactant comprises between 0.003M and 0.075M cetyltrimethylammonium bromide in the mixture.

9. The slurry of Claim 1, wherein the surfactant comprises cetyltrimethylammonium hydroxide dissolved in the mixture.

10. The slurry of Claim 1, wherein the surfactant comprises both cetyltrimethylammonium hydroxide and cetyltrimethylammonium bromide dissolved in the mixture.

11. (Amended) A copper polish slurry, comprising in combination:

B2 water, a surfactant containing an alkyltrimethylammonium cation, a chelating buffer system, an abrasive, an oxidizer, and a corrosion inhibitor, wherein the slurry has a pH between 2.5 and 7.0.

12. The method of Claim 11, wherein the abrasive comprises silica having a surface area 500 m²/g.

13. The method of Claim 12, wherein the corrosion inhibitor is selected from the group consisting of benzotriazole and cetyltrimethylammonium bromide.

14. The method of Claim 11, wherein the corrosion inhibitor is benzotriazole and the surfactant is selected from the group consisting of cetyltrimethylammonium bromide and cetyltrimethylammonium hydroxide.

B3 15. (Amended) The method of Claim 11, wherein the slurry has a density of 1.03 g/ml.

- Bad* 16. (Amended) The method of Claim 11, wherein the oxidizer comprises hydrogen peroxide; and the chelating buffer system comprises citric acid and potassium citrate.
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